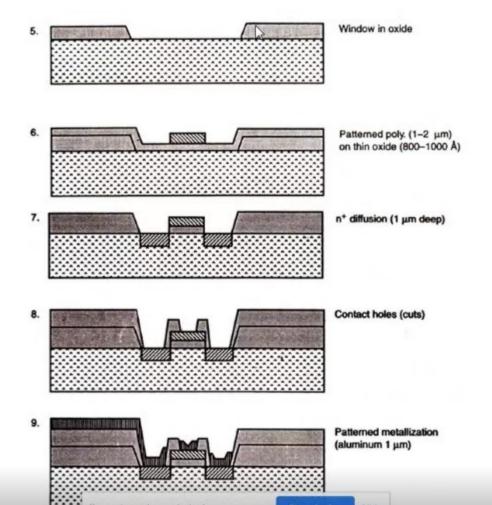
nMOS FABRICATION Thick oxide (1 µm) **Photoresist UV** light Mask



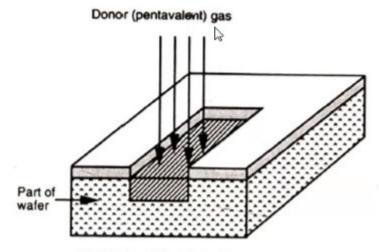
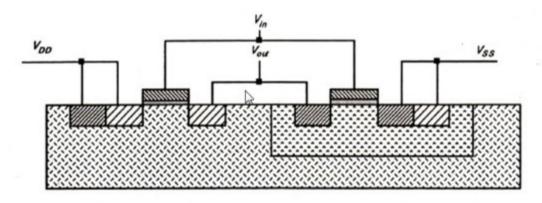
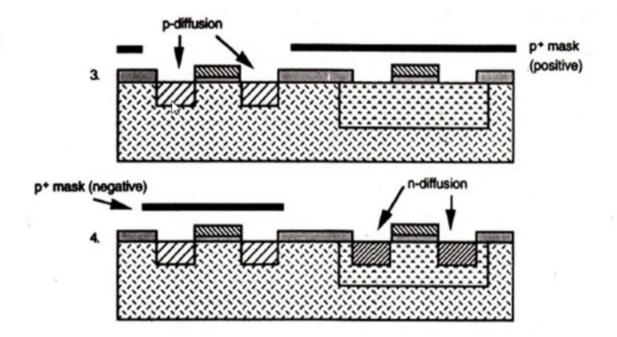


FIGURE 1.8 Diffusion process.



CMOS p-well inverter showing  $\emph{VDD}$  and  $\emph{VSS}$  substrate connections.



## **CMOS FABRICATION**

The p-well Process

